

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Koji SHIGEMATSU

Group Art Unit: Not yet Assigned

Application No.: Rule 53(b) Division of Application Examiner: Not yet Assigned
No. 09/234,969

Filed: November 28, 2000

Docket No.: 105192.01

For: PROJECTION OPTICAL SYSTEM AND EXPOSURE APPARATUS AND METHOD

PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Prior to initial examination on the merits, please amend the above-identified application as follows:

IN THE CLAIMS:

~~Please cancel claims 1-15, 19-30 and 33-37 without prejudice or disclaimer.~~

~~Please amend claims 16, 17, 31, 32 and 38 as follows:~~

~~16. (Amended) A method of patterning a photosensitive workpiece with a pattern present on a reticle, the method comprising the steps of:~~

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~~a) illuminating the reticle;~~

~~b) projecting light from said reticle with [the] a projection optical system,~~

~~[as set forth in claim 1] said projection optical system including, along an optical axis:~~

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~~i) a first lens group having positive refractive power,~~

~~ii) a second lens group having negative refractive power,~~